Phototriggered Micromanufacturing Using Photoresponsive Amorphous Spirooxazine Films

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Electronic Supplementary Information

ESI-1 DSC charts of SO1-SO5
ESI-2 Change in absorption spectra of SO1-SO5 during UV irradiation
ESI-3 $^1$H NMR spectra of prepared compounds
**Figure S1.** DSC charts of the amorphous glasses of SO1, SO2, SO3, SO4, and SO5.
ESI-2. Change in absorption spectra of SO1–SO5 during UV irradiation

Figure S2. Changes in the UV-vis absorption spectra of the SO film during irradiation with UV light (365 nm, 12 ± 1.0 mW cm$^{-2}$) under an air atmosphere at r.t. (a) SO1, (b) SO2, (c) SO3, (d) SO4, and (e) SO5.
ESI-3. ^1^H NMR spectra of prepared compounds
Figure S4  $^1$H NMR spectrum of SO$_3$ (300MHz, CDCl$_3$, TMS)
Figure S5  \(^1\)H NMR spectrum of SO₄ (300MHz, CDCl\(_3\), TMS)